



Docket No: Q60206

Group Art Unit: 1752

Examiner: J. Chu

## TC 1700

## PATENT APPLICATION

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Toshiaki AOAI, et al.

Appln. No.: 09/620,708

Confirmation No.: 3362

Filed: July 20, 2000

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET

**EXPOSURE** 

PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136

Commissioner for Patents Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one month, extending the time for responding to the Office Action of November 6, 2002 to March 6, 2003.

A check for the statutory fee of \$110.00 is attached. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

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WASHINGTON OFFICE

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PATENT TRADEMARK OFFICE

Date: March 5, 2003

Respectfully submitted,

Lee C. Wright

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